IN THE CLAIMS

Please amend claims 19, 24, 40, 41 and 46 as follows:

(TWICE AMENDED) A method of depositing diverse materials on individually electrodes comprising an array addressable electrode arrays, said method including the steps of:

<u>a)</u> providing an array of individually addressable electrodes, a power source, a reference electrode and a counter electrode;

b) delivering at least one source material to a predetermined <u>location</u> corresponding to one of said individually addressable electrodes [locations] on said array;

c) depositing a predetermined composition of said <u>at least one</u> source <u>material</u>
[materials] on a given electrode on said array;

d) performing said steps b) and c) at a plurality of different individually
electrodes
addressable arrays to produce a library of inorganic materials having different compositions at a
plurality of locations on said array; and

<u>e)</u> screening <u>each member of</u> said library of inorganic materials for a [useful property] <u>common selected property</u>.

A. (AMENDED) The method of claim [23] 12, wherein said [electrochemical deposition program is] depositing step (c) includes electrochemical deposition technique selected from the group consisting of potentiostatic reduction, potentiostatic oxidation, galvanostatic reduction, galvanostatic oxidation, potential square-wave voltammetry, and potential stair-step voltammetry.

2

540. (AMENDED) A method of depositing diverse materials on individually dectrodes comprising an array addressable cleetrode arrays and screening the same for a [useful] common selected property, said method including the steps of:

providing an array of individually addressable electrodes, a power source, a reference electrode and a counter electrode;

delivering a mixture of source materials to predetermined locations on said array corresponding to said individually addressable electrodes;

depositing a predetermined composition of said source materials on a given electrode on said array; and

repeating said depositing step to create a library of semiconductor-containing materials [within] on said array; and

screening <u>each member of</u> said library of semiconductor-containing materials for a <u>common selected</u> [catalytic] property.

A method of depositing diverse materials on individually electrode arrays and screening the same for a [useful] common selected property, said method including the steps of:

providing an array of individually addressable electrodes, a power source, a reference electrode and a counter electrode;

delivering a mixture of source materials to predetermined locations on said array corresponding to said individually addressable electrodes;

depositing a predetermined composition of said source materials on a given electrode on said array;

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repeating said depositing step to create a library of metal-containing materials [within] on said array; and

screening each member of said library of metal-containing materials for a common

selected eatalytic activity property.

materials at said locations.

c B4 46. (Amended) The method of claim 19, 46 or 41, wherein said depositing step includes varying the counter [anions] electrode at locations across the array to create different

Remarks

The Examiner has rejected the pending claims under 35 U.S.C. § 112. Without any concession as to the validity of the rejections, and in order to clarify the claims in accordance with the helpful suggestions of the Examiner, Applicants have amended claims 19, 24, 40, 41 and 46. In view of the amendments to the claims, it is believed all of the rejections have been obviated.

Because the amendments largely adopt the formal suggestions of the Examiner, upon the Examiner's thorough review of the Specification, it is presumed that basis for these amendments can be found throughout the specification, drawings, and claims as originally filed. As for the amendment to the specification, Applicants believe that to a skilled artisan, the context of the amended text makes it clear that Angstroms were intended, particularly in view of the text at page 7, lines 7-8. Accordingly, the present claims are fully supported by the specification.

Concerning the Examiner's rejection for alleged lack of enablement, Applicants respectfully trayerse. It appears that the Examiner has misapprehended the significance of the text at page 10,